

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	37	(sun near2 hee near2 kim).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2007/11/29 12:23
L2	9	(sun near2 hee near2 kim).in. and silicon	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2007/11/29 12:24
L3	3	(sun near2 hee near2 kim).in. and silicon and silane	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2007/11/29 12:26
L4	5	(soo near2 suk near2 lee).in. and silicon and silane	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2007/11/29 12:27
L5	52	(geun near2 bae near2 lim).in.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2007/11/29 12:27
L6	17	(geun near2 bae near2 lim).in. and silicon	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2007/11/29 12:27
L7	2	(geun near2 bae near2 lim).in. and silicon and silane	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2007/11/29 12:28
L8	6	(young near2 sun near2 lee).in. and silicon and silane	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2007/11/29 12:30
L9	204	silicon same silane same fluoro\$8 same (pecvd or cvd or vapor)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2007/11/29 12:31
L10	0	silicon same silane same fluoro\$8 same (pecvd or cvd or vapor) and fluoroalkylsilane	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2007/11/29 12:32
L11	5	silicon same silane same fluoro\$8 same (pecvd or cvd or vapor) and fluoroalkylsilane	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	OFF	2007/11/29 12:32

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- NEWS 6 JUL 16 CAplus enhanced with French and German abstracts
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- NEWS 9 JUL 30 USGENE now available on STN
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- NEWS 11 AUG 06 FSTA enhanced with new thesaurus edition
- NEWS 12 AUG 13 CA/Capplus enhanced with additional kind codes for granted patents
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- NEWS 16 AUG 28 CAS REGISTRY enhanced with additional experimental spectral property data
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- NEWS 19 SEP 13 INPADOCDB enhanced with monthly SDI frequency
- NEWS 20 SEP 17 CA/Capplus enhanced with printed CA page images from 1967-1998
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- NEWS 22 SEP 24 EMBASE, EMBAL, and LEMBASE reloaded with enhancements
- NEWS 23 OCT 02 CA/Capplus enhanced with pre-1907 records from Chemisches Zentralblatt
- NEWS 24 OCT 19 BEILSTEIN updated with new compounds
- NEWS 25 NOV 15 Derwent Indian patent publication number format enhanced
- NEWS 26 NOV 19 WPIX enhanced with XML display format
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FULL ESTIMATED COST	0.21	0.21

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Uploading C:\Program Files\Stnexp\Queries\10765366\str1.str

L1 STRUCTURE UPLOADED

=> s l1 full  
FULL SEARCH INITIATED 11:58:23 FILE 'REGISTRY'  
FULL SCREEN SEARCH COMPLETED - 501593 TO ITERATE

100.0% PROCESSED 501593 ITERATIONS 40926 ANSWERS  
SEARCH TIME: 00.00.03

L2 40926 SEA SSS FUL L1

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L3 STRUCTURE UPLOADED

=> s l3 full  
FULL SEARCH INITIATED 11:58:45 FILE 'REGISTRY'  
FULL SCREEN SEARCH COMPLETED - 22367 TO ITERATE

100.0% PROCESSED 22367 ITERATIONS 669 ANSWERS  
SEARCH TIME: 00.00.13

L4 669 SEA SSS FUL L3

=> file caplus  
COST IN U.S. DOLLARS SINCE FILE ENTRY TOTAL SESSION  
FULL ESTIMATED COST 344.20 344.41

FILE 'CAPLUS' ENTERED AT 11:59:27 ON 29 NOV 2007  
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FILE COVERS 1907 - 29 Nov 2007 VOL 147 ISS 23  
FILE LAST UPDATED: 28 Nov 2007 (20071128/ED)

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=> s 14 and 12  
1792 L4  
61465 L2  
L5 1792 L4 AND L2

=> s 15 and silicon  
854311 SILICON  
416 SILICONS  
854454 SILICON  
(SILICON OR SILICONS)  
L6 316 L5 AND SILICON

=> dup remove 16  
PROCESSING COMPLETED FOR L6  
L7 316 DUP REMOVE L6 (0 DUPLICATES REMOVED)

=> s 17 and (vapor)  
L8 316 S L7  
549461 VAPOR  
73279 VAPORS  
592558 VAPOR  
(VAPOR OR VAPORS)  
L9 51 L8 AND (VAPOR)

=> dup remove 19  
PROCESSING COMPLETED FOR L9  
L10 51 DUP REMOVE L9 (0 DUPLICATES REMOVED)

=> d ibib abs hitstr 1-5

L10 ANSWER 1 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
ACCESSION NUMBER: 2007:1000213 CAPLUS <<LOGINID::20071129>>  
DOCUMENT NUMBER: 147:355832  
TITLE: Digital magnetofluidic devices and methods  
INVENTOR(S): Hernandez, Sonia Melle; Gomez, Ana N.; Picraux, S.  
Thomas; Gust, John Devens; Hayes, Mark; Lindsay,  
Solitaire; Garcia, Antonio A.; Wang, Joseph;  
Vazquez-Alvarez, Terannie  
PATENT ASSIGNEE(S): Arizona Board of Regents for and on Behalf of Arizona  
State University, USA  
SOURCE: PCT Int. Appl., 118pp.  
CODEN: PIXXD2  
DOCUMENT TYPE: Patent  
LANGUAGE: English  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2007101174	A2	20070907	WO 2007-US62842	20070227
W:	AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LV, LY, MA, MD, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW			
RW:	AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM			

PRIORITY APPLN. INFO.: US 2006-777679P P 20060227

AB Disclosed are devices and methods for moving and controlling droplets of fluids on hydrophobic surfaces through the use of magnetic fields. For example, droplets can be moved, immobilized, dispensed, coalesced, and/or divided. Also disclosed is a digital magnetofluidic device comprising a hydrophobic surface; a magnetically active fluid droplet in contact with the surface; and a magnetic field coupled with at least a portion of the droplet. Also disclosed is a digital isoelec. focusing method using the devices and methods. Also disclosed are digital microelectrochem. detection methods and digital microelectrochem. reaction methods. This

abstr. is intended as a scanning tool for purposes of searching in the particular art and is not intended to be limiting of the present invention.

IT \*\*\*51851-37-7\*\*\* , 1H,1H,2H,2H-Perfluorooctyltriethoxysilane  
RL: RCT (Reactant); RACT (Reactant or reagent)  
(digital magnetofluidic devices and methods for controlling droplet movement)  
RN 51851-37-7 CAPLUS  
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA INDEX NAME)

/ Structure 1 in file .gra /

IT \*\*\*531506-10-2\*\*\* \*\*\*691013-81-7\*\*\* , 2-[3-(Triethoxysilyl)propylaminocarbonylamino]-6-methyl-4(1H)-pyrimidinone  
RL: TEM (Technical or engineered material use); USES (Uses)  
(digital magnetofluidic devices and methods for controlling droplet movement)  
RN 531506-10-2 CAPLUS  
CN 2-Propenoic acid, 2-methyl-, 3-(triethoxysilyl)propyl ester, polymer with .alpha.-(2-methyl-1-oxo-2-propen-1-yl)-.omega.-methoxypoly(oxy-1,2-ethanediyl), graft (CA INDEX NAME)  
  
CM 1  
  
CRN 26915-72-0  
CMF (C2 H4 O)n C5 H8 O2  
CCI PMS

/ Structure 2 in file .gra /

CM 2  
  
CRN 21142-29-0  
CMF C13 H26 O5 Si

/ Structure 3 in file .gra /

RN 691013-81-7 CAPLUS  
CN Urea, N-(1,6-dihydro-4-methyl-6-oxo-2-pyrimidinyl)-N'-[3-(triethoxysilyl)propyl]- (CA INDEX NAME)

/ Structure 4 in file .gra /

L10 ANSWER 2 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
ACCESSION NUMBER: 2007:933138 CAPLUS <<LOGINID::20071129>>  
DOCUMENT NUMBER: 147:290978  
TITLE: Method of processing a biological and/or chemical sample  
INVENTOR(S): Pipper, Juergen; Hsieh, Tseng-Ming; Neuzil, Pavel  
PATENT ASSIGNEE(S): Agency for Science, Technology and Research, Singapore  
SOURCE: PCT Int. Appl., 67pp.  
CODEN: PIXXD2  
DOCUMENT TYPE: Patent  
LANGUAGE: English  
FAMILY ACC. NUM. COUNT: 1  
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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WO 2007094739	A1	20070823	WO 2006-SG29	20060213
W:	AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, LY, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW			
RW:	AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH,			

GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY,  
KG, KZ, MD, RU, TJ, TM

PRIORITY APPLN. INFO.:

WO 2006-SG29

20060213

AB The invention provides a method of processing a biol. and/or chem. sample. The method includes providing a fluid droplet, which includes an inner phase and an outer phase. The outer phase is immiscible with the inner phase, and the outer phase is surrounding the inner phase. The inner phase includes the biol. and/or chem. sample. The fluid droplet also comprises magnetically attractable matter. The method also includes providing at least one surface, which is of such a texture and such a wettability for the fluid of the inner phase of the fluid droplet, that the fluid droplet remains intact upon being contacted therewith. The method further includes disposing the fluid droplet onto the at least one surface. The method also includes performing a process on the biol. and/or chem. sample in the fluid droplet.

IT \*\*\*101947-16-4\*\*\*

RL: MOA (Modifier or additive use); USES (Uses)

(method of processing biol. and/or chem. sample in fluid droplet)

RN 101947-16-4 CAPLUS

CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 5 in file .gra /

REFERENCE COUNT: 5 THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L10 ANSWER 3 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN

ACCESSION NUMBER: 2007:970042 CAPLUS <<LOGINID::20071129>>

DOCUMENT NUMBER: 147:288568

TITLE: Thin organic alignment layers with a batch process for liquid crystal displays

INVENTOR(S): Ong, Hiap L.

PATENT ASSIGNEE(S): Kyoritsu Optronics Co., Ltd., Taiwan

SOURCE: U.S. Pat. Appl. Publ., 16pp., Cont.-in-part of U.S. Ser. No. 227,570.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 2

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2007202253	A1	20070830	US 2006-607246	20061201
US 2007059438	A1	20070315	US 2005-227570	20050915

PRIORITY APPLN. INFO.:

US 2005-227570 A2 20050915

AB A method to form alignment layers on a substrate of an LCD is disclosed. The substrate is placed in a vacuum chamber and undergoes a purging process. The purging process heats the substrates and removes water \*\*\*vapor\*\*\* from the vacuum chamber. Specifically, the vacuum chamber is evacuated to a low pressure and refilled with a preheated inert gas. Evacuation of the vacuum chamber and refilling of the vacuum chamber is repeated several times. The alignment layer is then deposited using \*\*\*vapor\*\*\* deposition. Alternatively, plasma enhanced \*\*\*vapor\*\*\* deposition can be used for depositing the alignment layer. Furthermore, plasma cleaning prior to the deposition of the alignment layer can be used to clean the substrate.

IT \*\*\*2943-75-1\*\*\*, Octyltriethoxysilane \*\*\*51851-37-7\*\*\*,

1H,1H,2H,2H-Perfluorooctyltriethoxysilane

RL: TEM (Technical or engineered material use); USES (Uses)

(thin org. alignment layers with a batch process for liq. crystal displays)

RN 2943-75-1 CAPLUS

CN Silane, triethoxyoctyl- (CA INDEX NAME)

/ Structure 6 in file .gra /

RN 51851-37-7 CAPLUS

CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA INDEX NAME)

/ Structure 7 in file .gra /

L10 ANSWER 4 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
 ACCESSION NUMBER: 2007:980718 CAPLUS <<LOGINID::20071129>>  
 DOCUMENT NUMBER: 147:376451  
 TITLE: Method for constructing surface enhanced substrate  
 with metal ordered structure  
 INVENTOR(S): Lu, Nan; Yang, Bingjie; Huang, Chunyu; Chi, Lifeng  
 PATENT ASSIGNEE(S): Jilin University, Peop. Rep. China  
 SOURCE: Faming Zhuanli Shenqing Gongkai Shuomingshu, 30pp.  
 CODEN: CNXXEV  
 DOCUMENT TYPE: Patent  
 LANGUAGE: Chinese  
 FAMILY ACC. NUM. COUNT: 1  
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
CN 101024483	A	20070829	CN 2007-10055453	20070327
			CN 2007-10055453	20070327

PRIORITY APPLN. INFO.:

AB The invention relates to construct ordered structure on a substrate and metal ordered structure by using the ordered structure substrate as template, and the metal ordered structure can obviously enhance the probe mol. signal during the Raman detection process. The title method comprises: (1) selecting inorg. substrate or polymer substrate, cleaning, and treating to obtain conductive substrate, (2) constructing polymer barrier layer or different functional groups and ordered nano/micro structure by photolithog., electron beam etching, nano-imprinting, \*\*\*vapor\*\*\* deposition, self-assembly monolayer membrane, or LB membrane, (3) using the conductive substrate as work electrode, and electrodepositing under const. elec. voltage or current to obtain ordered metal nanoparticles array, and (4) immersing the work electrode in solvent to remove polymer layer, repeating for 3-4 times, and drying with high pure nitrogen to obtain the title substrate. The method can be used in construction of most metal ordered structure, which has wide application in prepg. high sensitivity metal sensor and detector, prepg. Raman substrate, and in Raman detection.

IT \*\*\*3069-42-9\*\*\*, Octadecyltrimethoxysilane \*\*\*101947-16-4\*\*\*, (Heptadecafluoro-1,1,2,2-tetrahydrodecyl)triethoxysilane  
 RL: NUU (Other use, unclassified); USES (Uses)  
 (method for constructing surface enhanced substrate with metal ordered structure)  
 RN 3069-42-9 CAPLUS  
 CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 8 in file .gra /

RN 101947-16-4 CAPLUS  
 CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 9 in file .gra /

L10 ANSWER 5 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
 ACCESSION NUMBER: 2007:157795 CAPLUS <<LOGINID::20071129>>  
 DOCUMENT NUMBER: 146:488210  
 TITLE: Surface Design for Precise Control of Spatial Growth  
 of a Mesostuctured Inorganic/Organic Film on a  
 Large-Scale Area  
 AUTHOR(S): Hozumi, Atsushi; Kojima, Satoshi; Nagano, Shusaku;  
 Seki, Takahiro; Shirahata, Naoto; Kameyama, Tetsuya  
 CORPORATE SOURCE: National Institute of Advanced Industrial Science  
 Technology (AIST), 2266-98 Anagahora, Shimo-shidami,  
 Moriyama-ku, Nagoya, 463-8560, Japan  
 SOURCE: Langmuir (2007), 23(6), 3265-3272  
 CODEN: LANGD5; ISSN: 0743-7463  
 PUBLISHER: American Chemical Society  
 DOCUMENT TYPE: Journal  
 LANGUAGE: English  
 AB A microfabrication technique is presented to fabricate a mesostructured inorg./org. composite film, i.e., silica/cetyltrimethylammonium chloride (CTAC) film, with near-perfect site-selectivity on a large surface area based on a spatially regulated growth method. To precisely regulate the site-selective growth of this mesocomposite film at the solid/liq. interface, we designed a novel microtemplate consisting of a

"dual-component" self-assembled monolayer (SAM) with alternating hydrophobic trifluorocarbon (CF<sub>3</sub>) and cationic amino (NH<sub>2</sub>) groups. First, (heptadecafluoro-1,1,2,2-tetrahydrodecyl)trimethoxysilane (FAS)-SAM was formed onto Si substrate covered with native oxide (SiO<sub>2</sub>/Si) from \*\*\*vapor\*\*\* phase. The substrate was then photolithog. micropatterned using 172 nm vacuum UV light. Finally, the micropatterned FAS-SAM was immersed in a soln. of 1 vol % (aminoethylaminomethyl)phenethyltrimethoxysilane (AEAMPS) in abs. toluene. Due to these treatments, a dual-SAM microtemplate with CF<sub>3</sub>- and NH<sub>2</sub>-terminated surfaces was fabricated, as evidenced by lateral force microscopy, ellipsometry, and XPS. Using this template, the microfabrication of a mesocomposite film was demonstrated. As a control, the micropatterned hydrophobic FAS-SAM template (composed of CF<sub>3</sub>- and OH-terminated surfaces) was also treated under the same conditions. Optical microscopy and at. force microscopy confirmed that the formation of the continuous mesocomposite film proceeded only on the FAS-SAM-covered regions, while the AEAMPS-SAM-covered regions remained free of deposits. This shielding effect also remained const. regardless of the pattern's geometry, i.e., the interval distance between the FAS-SAM-covered areas in the pattern. Through this approach, we were able to obtain well-defined 5-, 10-, and 20-.mu.m wide mesocomposite microlines over the entire 10 .times. 10 mm<sup>2</sup> area with high area-selectivity. On the other hand, when the SiO<sub>2</sub> regions were not terminated with the cationic NH<sub>2</sub> groups, cluster formation proceeded not only on the hydrophobic CF<sub>3</sub> regions but also on the SiO<sub>2</sub> regions, particularly with an increase in the pattern interval distance, resulting in lower final pattern resolu.

IT \*\*\*75822-22-9D\*\*\* , \*\*\*silicon\*\*\* bound \*\*\*83048-65-1D\*\*\* ,  
 (Heptadecafluoro-1,1,2,2-tetrahydrodecyl)trimethoxysilane, \*\*\*silicon\*\*\*  
 bound  
 RL: NUU (Other use, unclassified); PEP (Physical, engineering or chemical  
 process); PROC (Process); USES (Uses)  
 (prepn. of mesostructured inorg-org. composite film)  
 RN 75822-22-9 CAPLUS  
 CN 1,2-Ethanediamine, N1-[[4-[2-(trimethoxysilyl)ethyl]phenyl]methyl]- (CA  
 INDEX NAME)

/ Structure 10 in file .gra /

RN 83048-65-1 CAPLUS  
 CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
 heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 11 in file .gra /

REFERENCE COUNT: 81 THERE ARE 81 CITED REFERENCES AVAILABLE FOR THIS  
 RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

=> d hitstr 11-51

L10 ANSWER 11 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
 IT \*\*\*101947-16-4\*\*\* , 1H,1H,2H,2H-Perfluorodecyl triethoxysilane  
 RL: DEV (Device component use); PEP (Physical, engineering or chemical  
 process); PRP (Properties); PYP (Physical process); PROC (Process); USES  
 (Uses)  
 (surface modification of \*\*\*silicon\*\*\* and polydimethylsiloxane  
 surfaces with \*\*\*vapor\*\*\* -phase-deposited ultrathin fluorosilane  
 films for micro- and nanofluidic devices)  
 RN 101947-16-4 CAPLUS  
 CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
 heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 12 in file .gra /

L10 ANSWER 12 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
 IT \*\*\*101947-16-4\*\*\*  
 RL: PEP (Physical, engineering or chemical process); PYP (Physical  
 process); PROC (Process)  
 (hydrophobic agents; rain-proof glass windows with a \*\*\*silicon\*\*\*  
 -contg. hydrophobic surface of improved durability)  
 RN 101947-16-4 CAPLUS  
 CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
 heptadecafluorodecyl)- (CA INDEX NAME)



/ Structure 13 in file .gra /

L10 ANSWER 13 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*85712-15-8D\*\*\* , Methyloctyldimethoxysilane, \*\*\*silicon\*\*\* bound  
\*\*\*85857-17-6D\*\*\* , \*\*\*silicon\*\*\* bound  
RL: CPS (Chemical process); PEP (Physical, engineering or chemical  
process); PRP (Properties); PROC (Process)  
(prepn. of superhydrophobic SAM surface)  
RN 85712-15-8 CAPLUS  
CN Silane, dimethoxymethyloctyl- (CA INDEX NAME)

/ Structure 14 in file .gra /

RN 85857-17-6 CAPLUS  
CN Silane, dimethoxymethyl(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)-  
(9CI) (CA INDEX NAME)

/ Structure 15 in file .gra /

L10 ANSWER 14 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*101947-16-4\*\*\* , 1H,1H,2H,2H-Perfluorodecyltriethoxysilane  
RL: RCT (Reactant); RACT (Reactant or reagent)  
(micropatterning of SrBi2Ta2O9 ferroelec. thin films using selective  
deposition)  
RN 101947-16-4 CAPLUS  
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 16 in file .gra /

L10 ANSWER 15 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*101947-16-4\*\*\* , 1H,1H,2H,2H,-Perfluorodecyltriethoxysilane  
RL: BUU (Biological use, unclassified); BIOL (Biological study); USES  
(Uses)  
(nanoscale patterning of protein using electron beam lithog. of  
fluorinated organosilane self-assembled monolayers and high-affinity  
biotin-streptavidin binding system)  
RN 101947-16-4 CAPLUS  
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 17 in file .gra /

L10 ANSWER 16 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*83048-65-1\*\*\* , (Heptadecafluoro-1,1,2,2-tetrahydrodecyl)  
trimethoxysilane  
RL: CPS (Chemical process); PEP (Physical, engineering or chemical  
process); PROC (Process)  
(self-assembled monolayer; effect of oxide nanoskin on SAM formation on  
polymeric surface)  
RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 18 in file .gra /

L10 ANSWER 17 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*1067-25-0\*\*\* , Propyltrimethoxysilane \*\*\*101947-16-4\*\*\* ,  
Heptadecafluoro-1,1,2,2-tetrahydrodecyltriethoxysilane  
RL: MOA (Modifier or additive use); USES (Uses)  
(liq. and \*\*\*vapor\*\*\* phase silanes coating for release of thin  
film microelectromech. systems)  
RN 1067-25-0 CAPLUS  
CN Silane, trimethoxypropyl- (CA INDEX NAME)

/ Structure 19 in file .gra /

RN 101947-16-4 CAPLUS  
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 20 in file .gra /

L10 ANSWER 18 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*3069-21-4\*\*\* \*\*\*3069-40-7\*\*\* \*\*\*3069-42-9\*\*\* ,  
Octadecyltrimethoxysilane \*\*\*16415-12-6\*\*\* , HexadecyltrimethoxySilane  
\*\*\*83048-65-1\*\*\* , 2-(Perfluorooctyl)ethyltrimethoxysilane  
\*\*\*85857-16-5\*\*\* , 2-(Perfluorohexyl)ethyltrimethoxysilane  
RL: PEP (Physical, engineering or chemical process); PRP (Properties); PYP  
(Physical process); PROC (Process)  
(tribol. properties of organosilane monolayers prepd. by chem.  
\*\*\*vapor\*\*\* adsorption method on \*\*\*silicon\*\*\* substrates)  
RN 3069-21-4 CAPLUS  
CN Silane, dodecyltrimethoxy- (CA INDEX NAME)

/ Structure 21 in file .gra /

RN 3069-40-7 CAPLUS  
CN Silane, trimethoxyoctyl- (CA INDEX NAME)

/ Structure 22 in file .gra /

RN 3069-42-9 CAPLUS  
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 23 in file .gra /

RN 16415-12-6 CAPLUS  
CN Silane, hexadecyltrimethoxy- (CA INDEX NAME)

/ Structure 24 in file .gra /

RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 25 in file .gra /

RN 85857-16-5 CAPLUS  
CN Silane, trimethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA INDEX NAME)

/ Structure 26 in file .gra /

L10 ANSWER 19 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*159412-13-2\*\*\* \*\*\*208645-23-2\*\*\* \*\*\*805246-08-6\*\*\*  
\*\*\*805246-19-9\*\*\*  
RL: TEM (Technical or engineered material use); USES (Uses)  
(anti-stain film; anti-stain thin film formation onto glass, PET or  
cellulose triacetate film)  
RN 159412-13-2 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy-, homopolymer (CA INDEX NAME)  
  
CM 1  
  
CRN 83048-65-1  
CMF C13 H13 F17 O3 Si

/ Structure 27 in file .gra /

RN 208645-23-2 CAPLUS

CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)-, homopolymer (CA INDEX NAME)

CM 1

CRN 101947-16-4

CMF C16 H19 F17 O3 Si

/ Structure 28 in file .gra /

RN 805246-08-6 CAPLUS

CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)dimethoxymethyl-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 83038-84-0

CMF C13 H13 F17 O2 Si

/ Structure 29 in file .gra /

RN 805246-19-9 CAPLUS

CN Poly[oxy(1,1,2,2,3,3-hexafluoro-1,3-propanediyl)], .alpha.-(heptafluoropropyl)-.omega.-[1,1,2,2-tetrafluoro-4-(trimethoxysilyl)butoxy]-, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 365545-93-3

CMF (C3 F6 O)n C10 H13 F11 O4 Si

CCI PMS

/ Structure 30 in file .gra /

L10 ANSWER 20 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN

IT \*\*\*101947-16-4\*\*\* , Heptadecafluoro-1,1,2,2-tetrahydrodecyltriethoxysilane

RL: NUU (Other use, unclassified); USES (Uses)  
(coupling agent; method of coating microelectromech. devices)

RN 101947-16-4 CAPLUS

CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 31 in file .gra /

L10 ANSWER 21 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN

IT \*\*\*52686-75-6\*\*\* \*\*\*94237-08-8\*\*\* \*\*\*193674-11-2\*\*\*

RL: BUU (Biological use, unclassified); DEV (Device component use); BIOL  
(Biological study); USES (Uses)  
(development of substrate surface modification methods for biochem.  
immobilization in biochips)

RN 52686-75-6 CAPLUS

CN Silane, ethylmethoxydimethyl- (9CI) (CA INDEX NAME)

/ Structure 32 in file .gra /

RN 94237-08-8 CAPLUS

CN Silane, methoxydimethyl(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)-  
(CA INDEX NAME)

/ Structure 33 in file .gra /

RN 193674-11-2 CAPLUS

CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)methoxydimethyl- (CA INDEX NAME)

/ Structure 34 in file .gra /

L10 ANSWER 22 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*101947-16-4\*\*\* , AY 43-158E  
RL: RCT (Reactant); RACT (Reactant or reagent)  
(deposition from; method and app. for manufg. anti-reflective films)  
RN 101947-16-4 CAPLUS  
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 35 in file .gra /

L10 ANSWER 23 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*919-30-2\*\*\* , 3-Aminopropyltriethoxysilane \*\*\*3069-42-9\*\*\* ,  
Octadecyltrimethoxysilane \*\*\*83048-65-1\*\*\* , (Heptadecafluoro-1,1,2,2-tetrahydrodecyl)trimethoxysilane  
RL: ARU (Analytical role, unclassified); DEV (Device component use); PEP  
(Physical, engineering or chemical process); PYP (Physical process); ANST  
(Analytical study); PROC (Process); USES (Uses)  
(formation of mol. templates for fabricating on-chip biosensing devices)  
RN 919-30-2 CAPLUS  
CN 1-Propanamine, 3-(triethoxysilyl)- (CA INDEX NAME)

/ Structure 36 in file .gra /

RN 3069-42-9 CAPLUS  
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 37 in file .gra /

RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 38 in file .gra /

L10 ANSWER 24 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*3069-29-2\*\*\* , n-2-Aminoethyl-3-aminopropylmethyldimethoxysilane  
\*\*\*85857-16-5\*\*\* , 2-Perfluorohexyl ethyltrimethoxysilane  
RL: CPS (Chemical process); PEP (Physical, engineering or chemical process); PRP (Properties); PYP (Physical process); PROC (Process)  
(site-specific adsorption and arrangement of polystyrene microparticles on Si, patterned with organosilane monolayer through photolithog. process)  
RN 3069-29-2 CAPLUS  
CN 1,2-Ethanediamine, N1-[3-(dimethoxymethylsilyl)propyl]- (CA INDEX NAME)

/ Structure 39 in file .gra /

RN 85857-16-5 CAPLUS  
CN Silane, trimethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA INDEX NAME)

/ Structure 40 in file .gra /

L10 ANSWER 25 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*2530-83-8\*\*\* , (3-Glycidoxypropyl)trimethoxysilane \*\*\*51851-37-7\*\*\*  
, 1H,1H,2H,2H-Perfluorooctyltriethoxysilane  
RL: RCT (Reactant); RACT (Reactant or reagent)  
( \*\*\*vapor\*\*\* pressures of precursors for CVD of Si-based films)  
RN 2530-83-8 CAPLUS  
CN Oxirane, 2-[[3-(trimethoxysilyl)propoxy]methyl]- (CA INDEX NAME)

/ Structure 41 in file .gra /

RN 51851-37-7 CAPLUS  
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA INDEX NAME)

INDEX NAME)

/ Structure 42 in file .gra /

L10 ANSWER 26 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*18536-91-9\*\*\* , Dodecyltriethoxysilane \*\*\*101947-16-4\*\*\*  
RL: TEM (Technical or engineered material use); USES (Uses)  
(coating material; self-assembled monolayer coatings on nanostencils  
for redn. of contaminant adhesion)  
RN 18536-91-9 CAPLUS  
CN Silane, dodecyltriethoxy- (CA INDEX NAME)

/ Structure 43 in file .gra /

RN 101947-16-4 CAPLUS  
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 44 in file .gra /

L10 ANSWER 27 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*193756-76-2\*\*\*  
RL: MOA (Modifier or additive use); USES (Uses)  
(hydrophobic treatment agent; prepn. of hard, transparent and ultra  
water-repellent silica films by microwave plasma-enhanced CVD at low  
substrate temps. from trimethylmethoxysilane-CO2 gas mixts.)  
RN 193756-76-2 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy-, polymer with tetramethylsilane (9CI)  
(CA INDEX NAME)  
  
CM 1  
  
CRN 83048-65-1  
CMF C13 H13 F17 O3 Si

/ Structure 45 in file .gra /

CM 2  
  
CRN 75-76-3  
CMF C4 H12 Si

/ Structure 46 in file .gra /

L10 ANSWER 28 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*101947-16-4\*\*\* , (Heptadecafluoro-1,1,2,2-tetrahydro)decyl-  
triethoxysilane  
RL: CPS (Chemical process); PEP (Physical, engineering or chemical  
process); PROC (Process)  
(method for making thin film and electronic app.)  
RN 101947-16-4 CAPLUS  
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 47 in file .gra /

L10 ANSWER 29 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*51851-37-7\*\*\* , (Tridecafluoro-1, 1, 2, 2-tetrahydro) octyl  
triethoxysilane  
RL: CPS (Chemical process); PEP (Physical, engineering or chemical  
process); PROC (Process)  
(formation method of \*\*\*silicon\*\*\* thin film)  
RN 51851-37-7 CAPLUS  
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA  
INDEX NAME)

/ Structure 48 in file .gra /

L10 ANSWER 30 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*3069-42-9\*\*\* , n-Octadecyltrimethoxysilane \*\*\*51895-58-0\*\*\*  
\*\*\*83048-65-1\*\*\*  
RL: PEP (Physical, engineering or chemical process); PRP (Properties); PYP  
(Physical process); PROC (Process)  
(surface potential images of self-assembled monolayers patterned by  
organosilanes)  
RN 3069-42-9 CAPLUS  
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 49 in file .gra /

RN 51895-58-0 CAPLUS  
CN 1,6-Hexanediamine, N1-[3-(trimethoxysilyl)propyl]- (CA INDEX NAME)

/ Structure 50 in file .gra /

RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 51 in file .gra /

L10 ANSWER 31 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*3069-42-9\*\*\* , Octadecyltrimethoxysilane \*\*\*51895-58-0\*\*\*  
\*\*\*83048-65-1\*\*\*  
RL: CPS (Chemical process); PEP (Physical, engineering or chemical  
process); PROC (Process)  
(organosilane self-assembled monolayers formed at the \*\*\*vapor\*\*\*  
/solid interface)  
RN 3069-42-9 CAPLUS  
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 52 in file .gra /

RN 51895-58-0 CAPLUS  
CN 1,6-Hexanediamine, N1-[3-(trimethoxysilyl)propyl]- (CA INDEX NAME)

/ Structure 53 in file .gra /

RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 54 in file .gra /

L10 ANSWER 32 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*3069-42-9\*\*\* , Octadecyltrimethoxysilane \*\*\*83048-65-1\*\*\*  
RL: PRP (Properties); TEM (Technical or engineered material use); USES  
(Uses)  
(organosilane self-assembled monolayer photoresists for vacuum-UV  
lithog.)  
RN 3069-42-9 CAPLUS  
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 55 in file .gra /

RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 56 in file .gra /

L10 ANSWER 33 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*83048-65-1\*\*\* \*\*\*85857-16-5\*\*\*

RL: PRP (Properties)  
(lateral force and water contact angle on fluoroalkylsilane  
self-assembled monolayers dependent on mol. ordering)

RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 57 in file .gra /

RN 85857-16-5 CAPLUS  
CN Silane, trimethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA  
INDEX NAME)

/ Structure 58 in file .gra /

L10 ANSWER 34 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN

IT \*\*\*429-60-7\*\*\* , 3,3,3-Trifluoropropyltrimethoxysilane  
RL: PEP (Physical, engineering or chemical process); PRP (Properties); PYP  
(Physical process); PROC (Process)  
(activated; surface potential contrasts between Si surfaces covered and  
uncovered with organosilane self-assembled monolayer)

RN 429-60-7 CAPLUS  
CN Silane, trimethoxy(3,3,3-trifluoropropyl)- (CA INDEX NAME)

/ Structure 59 in file .gra /

IT \*\*\*3069-42-9\*\*\* , n-Octadecyltrimethoxysilane \*\*\*13822-56-5\*\*\* ,  
Aminopropyltrimethoxysilane \*\*\*83048-65-1\*\*\*  
RL: PEP (Physical, engineering or chemical process); PRP (Properties); PYP  
(Physical process); PROC (Process)  
(surface potential contrasts between Si surfaces covered and uncovered  
with organosilane self-assembled monolayer)

RN 3069-42-9 CAPLUS  
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 60 in file .gra /

RN 13822-56-5 CAPLUS  
CN 1-Propanamine, 3-(trimethoxysilyl)- (CA INDEX NAME)

/ Structure 61 in file .gra /

RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 62 in file .gra /

L10 ANSWER 35 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN

IT \*\*\*83048-65-1\*\*\*  
RL: PEP (Physical, engineering or chemical process); PROC (Process)  
(deposition of; in surface patterning by gathering hydrophilic fluid on  
latent pattern comprising hydrophilic region and water-repellent  
region)

RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 63 in file .gra /

L10 ANSWER 36 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN

IT \*\*\*3069-42-9\*\*\* , n-Octadecyltrimethoxysilane \*\*\*83048-65-1\*\*\* ,  
(Heptadecafluoro-1,1,2,2-tetrahydrodecyl) trimethoxysilane

RL: PEP (Physical, engineering or chemical process); PRP (Properties);  
PROC (Process)  
(zeta potentials of planar \*\*\*silicon\*\*\* plates covered with alkyl-  
and fluoroalkylsilane self-assembled monolayers)

RN 3069-42-9 CAPLUS  
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 64 in file .gra /

RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 65 in file .gra /

L10 ANSWER 37 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*83048-65-1\*\*\* , KBM 7803  
RL: DEV (Device component use); PEP (Physical, engineering or chemical  
process); PROC (Process); USES (Uses)  
(targets impregnated with; sintered metal targets impregnated with  
perfluoropolyether group-contg. alkoxysilanes for formation of  
antistaining and water-repellent coatings on antireflective materials)  
RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 66 in file .gra /

L10 ANSWER 38 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*3069-42-9\*\*\* , Octadecyltrimethoxysilane \*\*\*83048-65-1\*\*\*  
RL: PEP (Physical, engineering or chemical process); PROC (Process)  
(micropatterning of \*\*\*silicon\*\*\* substrates using alkyl- and  
fluoroalkylsilane self-assembled monolayers and vacuum-UV)  
RN 3069-42-9 CAPLUS  
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 67 in file .gra /

RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 68 in file .gra /

L10 ANSWER 39 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*3069-42-9\*\*\* , Octadecyl-trimethoxysilane \*\*\*83048-65-1\*\*\*  
RL: PEP (Physical, engineering or chemical process); PROC (Process)  
(hydrophobic layer precursor; effects of surface functional groups and  
microstructures on morphol. of mesoporous silica grown on org.  
surfaces)  
RN 3069-42-9 CAPLUS  
CN Silane, trimethoxyoctadecyl- (CA INDEX NAME)

/ Structure 69 in file .gra /

RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 70 in file .gra /

L10 ANSWER 40 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*190579-86-3\*\*\* , Triethoxy(3,3,4,4,5,5,6,6,7,7,7-  
undecafluoroheptyl)silane  
RL: TEM (Technical or engineered material use); USES (Uses)  
(manuf. of water-repellent coatings on optical substrates by



electron-beam \*\*\*vapor\*\*\* deposition of org. \*\*\*silicon\*\*\*  
comps. impregnated in porous carriers)  
RN 190579-86-3 CAPLUS  
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,7-undecafluoroheptyl)- (CA INDEX  
NAME)

/ Structure 71 in file .gra /

L10 ANSWER 41 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*83048-65-1\*\*\* , KBM7803  
RL: NUU (Other use, unclassified); PEP (Physical, engineering or chemical  
process); PROC (Process); USES (Uses)  
(in manuf. of water-repellent \*\*\*silicon\*\*\* oxide film)  
RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 72 in file .gra /

L10 ANSWER 42 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*83048-65-1\*\*\*  
RL: NUU (Other use, unclassified); PEP (Physical, engineering or chemical  
process); PROC (Process); USES (Uses)  
(precursor; microwave plasma CVD for transparent and hard Si oxide  
films with graded compn.)  
RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 73 in file .gra /

L10 ANSWER 43 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*83048-65-1\*\*\*  
RL: DEV (Device component use); PEP (Physical, engineering or chemical  
process); PRP (Properties); PROC (Process); USES (Uses)  
(final precursor gas contg.; prepn. of \*\*\*silicon\*\*\* oxide films  
having a water-repellent surface by multiple-step microwave  
plasma-enhanced chem. \*\*\*vapor\*\*\* deposition)  
RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 74 in file .gra /

L10 ANSWER 44 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*83048-65-1\*\*\*  
RL: MOA (Modifier or additive use); PEP (Physical, engineering or chemical  
process); PROC (Process); USES (Uses)  
(effects of Me and perfluoroalkyl groups on water repellency of  
\*\*\*silicon\*\*\* oxide films prepd. by microwave plasma-enhanced CVD)  
RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 75 in file .gra /

L10 ANSWER 45 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*101947-16-4\*\*\* , 1H,1H,2H,2H,-Perfluorodecyltriethoxysilane  
RL: PEP (Physical, engineering or chemical process); PRP (Properties);  
PROC (Process)  
( \*\*\*vapor\*\*\* phase silylation of, on germanium/germanium oxide  
surfaces, mol. orientation in thin films and surface coverage of)  
RN 101947-16-4 CAPLUS  
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)- (CA INDEX NAME)

/ Structure 76 in file .gra /

L10 ANSWER 46 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*429-60-7\*\*\* \*\*\*83048-65-1\*\*\* \*\*\*85857-16-5\*\*\*  
RL: PEP (Physical, engineering or chemical process); PROC (Process)  
(precursor; coating of transparent water-repellent thin films by  
plasma-enhanced CVD)  
RN 429-60-7 CAPLUS  
CN Silane, trimethoxy(3,3,3-trifluoropropyl)- (CA INDEX NAME)

/ Structure 77 in file .gra /

RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 78 in file .gra /

RN 85857-16-5 CAPLUS  
CN Silane, trimethoxy(3,3,4,4,5,5,6,6,7,7,8,8,8-tridecafluorooctyl)- (CA  
INDEX NAME)

/ Structure 79 in file .gra /

L10 ANSWER 47 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*159412-13-2P\*\*\*  
RL: IMF (Industrial manufacture); TEM (Technical or engineered material  
use); PREP (Preparation); USES (Uses)  
(manuf. of water-repellent coatings on resin substrates by high  
frequency plasma \*\*\*vapor\*\*\* deposition of perfluoroalkylsilanes)  
RN 159412-13-2 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy-, homopolymer (CA INDEX NAME)  
  
CM 1  
  
CRN 83048-65-1  
CMF C13 H13 F17 O3 Si

/ Structure 80 in file .gra /

IT \*\*\*83048-65-1\*\*\* , KBM 7803  
RL: PEP (Physical, engineering or chemical process); PROC (Process)  
(manuf. of water-repellent coatings on resin substrates by high  
frequency plasma \*\*\*vapor\*\*\* deposition of perfluoroalkylsilanes)  
RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 81 in file .gra /

L10 ANSWER 48 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*159412-13-2\*\*\* , (Heptadecafluoro-1,1,2,2-tetrahydrodecyl)-1-  
trimethoxysilane homopolymer  
RL: PEP (Physical, engineering or chemical process); TEM (Technical or  
engineered material use); PROC (Process); USES (Uses)  
(plasma-enhanced chem. \*\*\*vapor\*\*\* deposition of water-repellent  
and transparent fluorine-contg. films on polycarbonate and  
\*\*\*silicon\*\*\* and glass)  
RN 159412-13-2 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy-, homopolymer (CA INDEX NAME)  
  
CM 1  
  
CRN 83048-65-1  
CMF C13 H13 F17 O3 Si

/ Structure 82 in file .gra /

L10 ANSWER 49 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*83048-65-1\*\*\*  
RL: PEP (Physical, engineering or chemical process); PRP (Properties);  
PROC (Process)  
(effects of substrate temp. on properties of fluorine contained  
\*\*\*silicon\*\*\* oxide films prepd. by microwave plasma-enhanced CVD)  
RN 83048-65-1 CAPLUS  
CN Silane, (3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)trimethoxy- (CA INDEX NAME)

/ Structure 83 in file .gra /

L10 ANSWER 50 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*160687-77-4P\*\*\* \*\*\*160718-35-4P\*\*\*  
RL: IMF (Industrial manufacture); TEM (Technical or engineered material  
use); PREP (Preparation); USES (Uses)  
(water-repellent fluorine-contg. \*\*\*silicon\*\*\* oxide coatings on  
glass and \*\*\*silicon\*\*\* wafer)  
RN 160687-77-4 CAPLUS  
CN Silicic acid (H4SiO4), tetramethyl ester, polymer with  
triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-heptadecafluorodecyl)silane  
(9CI) (CA INDEX NAME)  
  
CM 1  
  
CRN 101947-16-4  
CMF C16 H19 F17 O3 Si

/ Structure 84 in file .gra /

CM 2  
  
CRN 681-84-5  
CMF C4 H12 O4 Si

/ Structure 85 in file .gra /

RN 160718-35-4 CAPLUS  
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)-, polymer with silane (9CI) (CA INDEX NAME)  
  
CM 1  
  
CRN 101947-16-4  
CMF C16 H19 F17 O3 Si

/ Structure 86 in file .gra /

CM 2  
  
CRN 7803-62-5  
CMF H4 Si

/ Structure 87 in file .gra /

L10 ANSWER 51 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
IT \*\*\*101947-16-4\*\*\*  
RL: RCT (Reactant); RACT (Reactant or reagent)  
(reaction of, with \*\*\*silicon\*\*\* surface, in prepn. of polyimide  
thin film)  
RN 101947-16-4 CAPLUS  
CN Silane, triethoxy(3,3,4,4,5,5,6,6,7,7,8,8,9,9,10,10,10-  
heptadecafluorodecyl)- (CA INDEX NAME)

=> d bib 13, 17, 18, 21, 46

L10 ANSWER 13 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
 AN 2005:106536 CAPLUS <<LOGINID::20071129>>  
 DN 142:361489  
 TI Fabrication of Superhydrophobic Surfaces by Self-Assembly and Their  
 Water-Adhesion Properties  
 AU Song, Xiaoyan; Zhai, Jin; Wang, Yilin; Jiang, Lei  
 CS Center for Molecular Sciences, Institute of Chemistry, Chinese Academy of  
 Sciences, Beijing, 100080, Peop. Rep. China  
 SO Journal of Physical Chemistry B (2005), 109(9), 4048-4052  
 CODEN: JPCBFK; ISSN: 1520-6106  
 PB American Chemical Society  
 DT Journal  
 LA English  
 RE.CNT 31 THERE ARE 31 CITED REFERENCES AVAILABLE FOR THIS RECORD  
 ALL CITATIONS AVAILABLE IN THE RE FORMAT

L10 ANSWER 17 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
 AN 2006:143210 CAPLUS <<LOGINID::20071129>>  
 DN 144:499593  
 TI Liquid and \*\*\*vapor\*\*\* phase silanes coating for the release of thin  
 film MEMS  
 AU Parvais, B.; Pallandre, A.; Jonas, A. M.; Raskin, J.-P.  
 CS Research Center in Micro and Nanoscopic Materials and Electronic Devices  
 (CERMIN), Universite catholique de Louvain, Louvain-la-Neuve, B-1348,  
 Belg.  
 SO IEEE Trans. Device Mater. Reliab. (2005), 5(2), 250-254  
 CODEN: ITDMA2; ISSN: 1530-4388  
 URL: <http://ieeexplore.ieee.org/iel5/7298/31396/01458741.pdf?isnumber=31396&prod=JNL&arnumber=1458741&arSt=+250&ared=+254&arAuthor=Parvais%2C+B.%3B+Pallandre%2C+A.%3B+Jonas%2C+A.M.%3B+Raskin%2C+J.-P.>  
 PB Institute of Electrical and Electronics Engineers  
 DT Journal; (online computer file)  
 LA English  
 RE.CNT 18 THERE ARE 18 CITED REFERENCES AVAILABLE FOR THIS RECORD  
 ALL CITATIONS AVAILABLE IN THE RE FORMAT

L10 ANSWER 18 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
 AN 2005:422268 CAPLUS <<LOGINID::20071129>>  
 DN 144:281105  
 TI Macro- and nanotribological properties of organosilane monolayers prepared  
 by a chemical \*\*\*vapor\*\*\* adsorption method on \*\*\*silicon\*\*\*  
 substrates  
 AU Ishida, H.; Koga, T.; Morita, M.; Otsuka, H.; Takahara, A.  
 CS Graduate School of Engineering, Kyushu University, Fukuoka, 812-8581,  
 Japan  
 SO Tribology Letters (2005), 19(1), 3-8  
 CODEN: TRLEFS; ISSN: 1023-8883  
 PB Springer  
 DT Journal  
 LA English  
 RE.CNT 21 THERE ARE 21 CITED REFERENCES AVAILABLE FOR THIS RECORD  
 ALL CITATIONS AVAILABLE IN THE RE FORMAT

L10 ANSWER 21 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
 AN 2004:674693 CAPLUS <<LOGINID::20071129>>  
 DN 141:168967  
 TI Development of substrate surface modification methods for biochemical  
 immobilization in biochips  
 IN Kim, Hun-Ki; Lee, Jung-Suk; Lim, Geun-Bae; Lee, Young-Sun  
 PA Samsung Electronics Co., Ltd., S. Korea  
 SO Jpn. Kokai Tokkyo Koho, 11 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2004229663	A	20040819	JP 2004-18353	20040127
	KR 2004069063	A	20040804	KR 2003-5486	20030128
	EP 1452232	A2	20040901	EP 2004-1606	20040126
	EP 1452232	A3	20050720		

R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,  
IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK

US 2004185480	A1	20040923	US 2004-765366	20040127
CN 1519562	A	20040811	CN 2004-10005810	20040128
PRAI KR 2003-5486	A	20030128		

L10 ANSWER 46 OF 51 CAPLUS COPYRIGHT 2007 ACS on STN  
AN 1997:622716 CAPLUS <<LOGINID::20071129>>  
DN 127:310357  
TI Coating of transparent water-repellent thin films by plasma-enhanced CVD  
AU Takai, Osamu; Hozumi, Atsushi; Sugimoto, Nobuhisa  
CS Department of Materials Processing Engineering, Nagoya University,  
Chikusa-ku, Nagoya, 464-01, Japan  
SO Journal of Non-Crystalline Solids (1997), 218, 280-285  
CODEN: JNCSBJ; ISSN: 0022-3093  
PB Elsevier  
DT Journal  
LA English  
RE.CNT 12 THERE ARE 12 CITED REFERENCES AVAILABLE FOR THIS RECORD  
ALL CITATIONS AVAILABLE IN THE RE FORMAT

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ENTRY	SESSION
-3.90	-3.90

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SINCE FILE	TOTAL
ENTRY	SESSION
0.18	488.42

FULL ESTIMATED COST

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)

SINCE FILE	TOTAL
ENTRY	SESSION
0.00	-3.90

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NEWS	4	MAY 14	RDISCLOSURE on STN Easy enhanced with new search and display fields
NEWS	5	MAY 21	BIOSIS reloaded and enhanced with archival data
NEWS	6	MAY 21	TOXCENTER enhanced with BIOSIS reload
NEWS	7	MAY 21	CA/CAPplus enhanced with additional kind codes for German patents
NEWS	8	MAY 22	CA/CAPplus enhanced with IPC reclassification in Japanese patents
NEWS	9	JUN 27	CA/CAPplus enhanced with pre-1967 CAS Registry Numbers
NEWS	10	JUN 29	STN Viewer now available
NEWS	11	JUN 29	STN Express, Version 8.2, now available
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NEWS	13	JUL 02	LMEDLINE coverage updated
NEWS	14	JUL 02	SCISEARCH enhanced with complete author names
NEWS	15	JUL 02	CHEMCATS accession numbers revised
NEWS	16	JUL 02	CA/CAPplus enhanced with utility model patents from China
NEWS	17	JUL 16	Caplus enhanced with French and German abstracts
NEWS	18	JUL 18	CA/CAPplus patent coverage enhanced
NEWS	19	JUL 26	USPATFULL/USPAT2 enhanced with IPC reclassification
NEWS	20	JUL 30	USGENE now available on STN
NEWS	21	AUG 06	CAS REGISTRY enhanced with new experimental property tags
NEWS	22	AUG 06	BEILSTEIN updated with new compounds
NEWS	23	AUG 06	FSTA enhanced with new thesaurus edition
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NEWS	25	AUG 20	CA/CAPplus enhanced with CAS indexing in pre-1907 records
NEWS	26	AUG 27	Full-text patent databases enhanced with predefined patent family display formats from INPADOCDB
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NEWS	28	AUG 28	CAS REGISTRY enhanced with additional experimental spectral property data

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